

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended) A substrate processing apparatus, comprising:

a carrier block including a carrier placement portion to/from which a substrate carrier storing a plurality of substrates is loaded/unloaded, and first transfer means for performing delivery of the substrate with respect to the substrate carrier placed on the carrier placement portion;

a transfer block comprising second transfer means provided adjacent to the carrier block and for transferring the substrate along a linear transfer path, said transfer block including at least one utility unit including a plurality of connection ends for supplying utilities;

a first delivery stage for performing delivery of the substrate between said first transfer means and said second transfer means;

a plurality of process blocks arranged along said transfer path ~~[[and]]~~, wherein each process block is freely attachable/detachable with respect to the transfer block, and wherein each process block includes at least one connection end which is freely attachable/detachable to a connection end of the at least one utility unit to receive utilities from the transfer block a ~~main body of the apparatus;~~ and

an interface portion located between said transfer path and a light exposure machine;

each process block including a coating unit for applying a resist solution to the substrate, a developing unit for performing developing processing on the substrate after exposure to light, a heating unit for heating the substrate, third transfer means for transferring the substrate between the units, and a second delivery stage for performing delivery of the substrate between said second transfer means and said third transfer means,

said transfer path extending from said interface portion to said carrier block, with said plurality of process blocks arranged on only one side of said transfer path, and each of said plurality of process blocks performing same processing, and

application of the resist solution to the substrate and/or the developing processing after exposure to light being performed in units of the respective process blocks.

Claim 2 (Previously Presented): The substrate processing apparatus according to claim 1, wherein an interface portion to which a light exposure device is connected is connected to a side of said transfer path opposite to a side connected to the carrier block.

Claim 3 (Previously Presented): The substrate processing apparatus according to claim 1, wherein an interface portion to which a light exposure device is connected is connected to a side of said transfer path opposite to a side connected to the process blocks.

Claim 4 (Currently Amended): A substrate processing apparatus, comprising:
a carrier block including a carrier placement portion to/from which a substrate carrier storing a plurality of substrates is loaded/unloaded, and first transfer means for performing delivery of the substrate with respect to the substrate carrier placed on the carrier placement portion;

a transfer block comprising second transfer means provided adjacent to the carrier block and for transferring the substrate along a linear transfer path, said transfer block including at least one utility unit including a plurality of connection ends for supplying utilities;

a first delivery stage for performing delivery of the substrate between said first transfer means and said second transfer means;

a plurality of process blocks arranged along said transfer path ~~[[and]], wherein each process block is~~ freely attachable/detachable with respect to the transfer block, and wherein each process block includes at least one connection end which is freely attachable/detachable to a connection end of the at least one utility unit to receive utilities from the transfer block ~~with respect to a main body of the apparatus~~; and

an interface portion located between said transfer path and a light exposure machine;

each process block including a liquid process unit performing processing with a chemical solution on the substrate, a heating unit for heating the substrate, third transfer means for transferring the substrate between the units, and a second delivery stage for performing delivery of the substrate between said second transfer means and said third transfer means,

said transfer path extending from said interface portion to said carrier block, with said plurality of process blocks arranged on only one side of said transfer path, and each of said plurality of process blocks performing same processing, and

processing being performed on the substrate in units of the respective process blocks.

Claim 5 (Previously Presented): The substrate processing apparatus according to claim 4, wherein said liquid process unit is for forming a coating film.

Claim 6 (Currently Amended): The substrate processing apparatus according to claim 4, wherein said liquid process unit is for applying a chemical solution including a precursor of an insulating film to the substrate.

Claim 7 (Previously Presented): The substrate processing apparatus according to claim 4, wherein said plurality of process blocks are formed to have a same size in two dimensions.

Claim 8 (Canceled).

Claim 9 (Currently Amended): The substrate processing apparatus according to claim ~~[[8]]~~ 4, wherein said carrier block is capable of rotating about a rotation shaft provided at an end portion of said transfer block.

Claim 10 (Currently Amended): The substrate processing apparatus according to claim ~~[[8]]~~ 4, wherein said process block is attached to said transfer block via a hinge, and rotated about said hinge to be positioned in place.

Claim 11 (Previously Presented): The substrate processing apparatus according to claim 4, comprising a positioning member provided at a bottom portion or a side portion of a region where said process block is to be arranged, for use in positioning said process block.

Claim 12 (Previously Presented): The substrate processing apparatus according to claim 4, comprising a guide member provided at a bottom portion or a side portion of a region where said process block is to be arranged, for use in drawing the process block, and a positioning member provided for positioning the process block to the guide member.

Claim 13 (Canceled).

Claim 14 (Currently Amended): The substrate processing apparatus according to claim [[13]] 4, wherein each process block includes a plurality of connection ends freely attachable/detachable to connection ends of the transfer block, and wherein the connection ends of each process block are connected to a plurality of utility lines of each process block, and further wherein said plurality of utility lines supply utilities different from each other, and each of the plurality of utility lines is branched on a downstream side to be guided to the respective process units.

Claim 15 (Currently Amended): The substrate processing apparatus according to claim [[13]] 14, wherein the plurality of utility lines include a supply line of liquid for temperature regulation, a supply line of inactive gas, an electric supply line, and a signal line.

Claim 16 (Currently Amended): The substrate processing apparatus according to claim 4, wherein [[a]] the plurality of connection ends include a first connection end on an external side which is provided at a lower side of the transfer block ~~second transfer means~~, and wherein the first connection end [[it]] is configured such that when the process block is pressed to the transfer block ~~second transfer means side~~, the first connection end on the external side is connected to a connection end on the process block side.

Claim 17 (Currently Amended): The substrate processing apparatus according to claim [[16]] 15, wherein the utility lines further include a chemical solution supply tube.

Claim 18 (New): The substrate processing apparatus according to claim 1, wherein the at least one connection end of each process block includes a plurality of connection ends

respectively connectable to connection ends of the transfer block for supplying a plurality of different utilities from the transfer block to each of the process blocks.

Claim 19 (New): The substrate processing apparatus according to claim 4, wherein the at least one connection end of each process block includes a plurality of connection ends respectively connectable to connection ends of the transfer block for supplying a plurality of different utilities from the transfer block to each of the process blocks.

Claim 20 (New): A substrate processing apparatus, comprising:

a carrier block including a carrier placement portion to/from which a substrate carrier storing a plurality of substrates is loaded/unloaded, and a first transfer apparatus which delivers substrates with respect to the substrate carrier placed on the carrier placement portion;

at transfer block, said transfer block comprising a second transfer apparatus for carrying substrates along a transfer path, the transfer block further including a plurality of process block receiving sites, and wherein a utilities connection site is associated with each of said plurality of process block receiving sites, each utilities connection site including a plurality of connection ends for supplying a plurality of different utilities;

at least one process block arranged along said transfer path and freely attachable/detachable to the transfer block at one of the process block receiving sites, said process block including a utilities connection site which is attachable/detachable to a utilities connection site of the transfer block, wherein the utilities connection site of the process block includes a plurality of connection ends for receiving a plurality of different utilities from the connection ends of a utilities site of the transfer block;

wherein at least one process block includes a plurality of process units which perform at least one of a resist application process or a developing process, said process block further including a third transfer apparatus which transfers wafers within the process block; and

wherein said transfer path extends from said carrier block and along each of the plurality of process block receiving sites.

Claim 21 (New): The substrate processing apparatus of claim 20, wherein said carrier block is movably mounted to said transfer block such that the carrier block is movable between an operational position and a non-operational position, and wherein in said non-operational position additional space is provided at at least one of the process block receiving sites to facilitate attachment and detachment of a process block to the transfer block.

Claim 22 (New): The substrate processing apparatus of claim 20, wherein the process block includes at least one resist application unit, at least one developing unit, and at least one heating unit; and

wherein said plurality of connection ends of transfer block include at least one connection end for supplying electricity from the transfer block to the process block, at least one liquid supply connection end for supplying a liquid from the transfer block to the process block, and at least one signal connection end for providing a signal from the transfer block to the process block.

Claim 23 (New): The substrate processing apparatus of claim 22, further including a guide associated with each of the process block receiving sites, and wherein the utilities connection sites and the guides are configured such that as a process block is guided toward

and urged against the transfer block, one of the utilities connection sites of the transfer block is connected to the utilities connection site of the process block.